



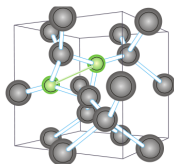
Update on RD50 project NitroStrip

Marta Baselga, 31st RD50 Workshop, CERN

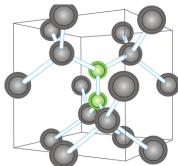
ETP -KIT



- As shown in previous RD50 Workshops Nitrogen enriched wafers show promising behaviour after irradiation:
 - The concentrations of defect centers with the activation energies of 30 meV, 310 meV, 360 meV, 380 meV, and 460 meV are found to be significantly lower in the material with a higher nitrogen concentration



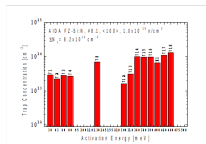
N_2 dimer
two split-interstitials



N_2 pair
 N_i + split-interstitial

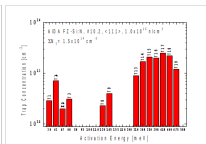
• R. Jones *et al.* Solid State Phenomena 93, (2004) 95-96

Sample E, $[N] = 2.5 \times 10^{19} \text{ cm}^{-3}$



Total trap concentration: $2.5 \times 10^{14} \text{ cm}^{-3}$

Sample F, $[N] = 2.5 \times 10^{20} \text{ cm}^{-3}$



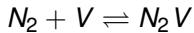
Total trap concentration: $2.5 \times 10^{15} \text{ cm}^{-3}$

[Kaminski, RD50 Workshop, November 2014]

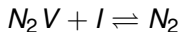
- Fluence $1 \times 10^{15} \text{ neq/cm}^2$

Suppression of interstitials and vacancy-related defects for FZ-Si with nitrogen

Dominant reaction for vacancy suppression:¹



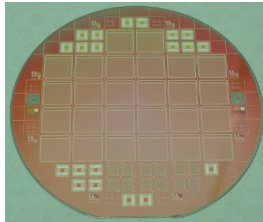
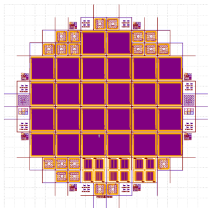
Suppression of interstitials aggregation:



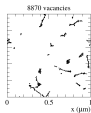
¹W. von Ammon et al. J. Cryst. Growth 226, 19 (2001)

Fabrication NitroStrip at CNM

Wafers	Label	Substrate
1-6	FZ	HR-FZ 100 mm, <100>, n-type (phosphorus), 2000-2400 Ω cm 300 \pm 15 μ m, 1 side polished
7-12	NIT	HR-FZ Nitrogenated 100 mm, <100>, n-type (phosphorus), 1500-1900 Ω cm 300 \pm 15 μ m, 1 side polished
13-18	DOFZ	HR-FZ Oxygenated Same as FZ but oxygenated
19-24	MCz	HR-MCz 100 mm, <100>, n-type (phosphorus), 800-1000 Ω cm 300 \pm 15 μ m, 2 side polished



[RD50 NitroStrip: First C-V and I-V results on run 9802 diodes and microstrips, J-M Rafi, 2017]



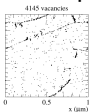
1 MeV Neutron

Ljubljana neutrons



10 MeV Proton

KIT 23 MeV protons



24 GeV/c Proton

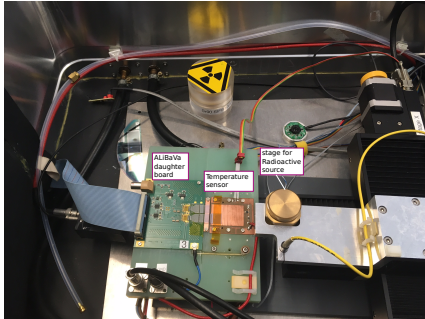
CERN 24 GeV protons

[Huhtinen CERN 2001, Si-RadHard Workshop]

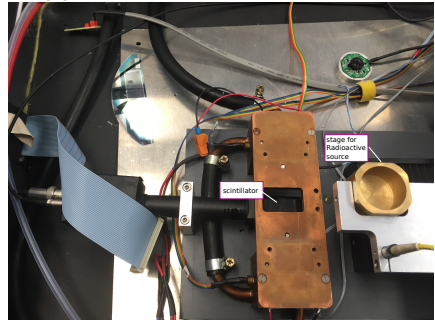
Fluences

$2 \cdot 10^{11} n_{eq} / \text{cm}^2$
$5 \cdot 10^{12} n_{eq} / \text{cm}^2$
$1 \cdot 10^{13} n_{eq} / \text{cm}^2$
$5 \cdot 10^{13} n_{eq} / \text{cm}^2$
$1 \cdot 10^{14} n_{eq} / \text{cm}^2$
$3 \cdot 10^{14} n_{eq} / \text{cm}^2$
$6 \cdot 10^{14} n_{eq} / \text{cm}^2$
$1 \cdot 10^{15} n_{eq} / \text{cm}^2$

ALiBaVa Board



Support and scintillator

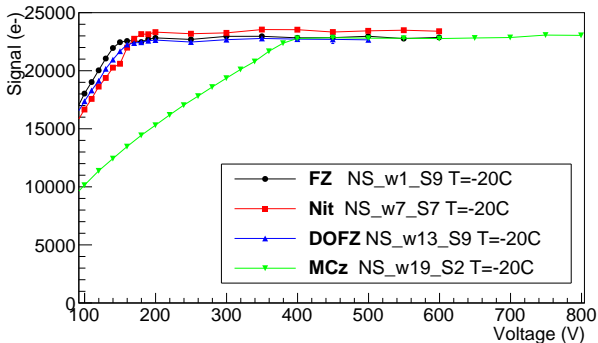


ALiBaVa measurements unirradiated sensors

Measurements taken with the same ALiBaVa board and ^{90}Sr radioactive source

Trigger events 100000

NitroStrip ALiBaVa measurements: Without irradiation



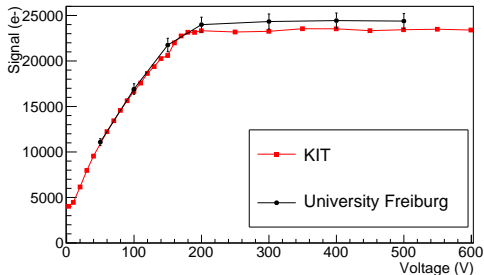
Once depleted, the detectors have:

- FZ $\sim 23\text{ke}^-$
- Nit $\sim 23.5\text{ke}^-$
- DOFZ $\sim 23\text{ke}^-$
- MCz $\sim 23\text{ke}^-$

Measurement uncertainty estimated to be $\sim 5\%$

Comparison between KIT and University Freiburg measurements

Nitrogen enriched wafer, without irradiation

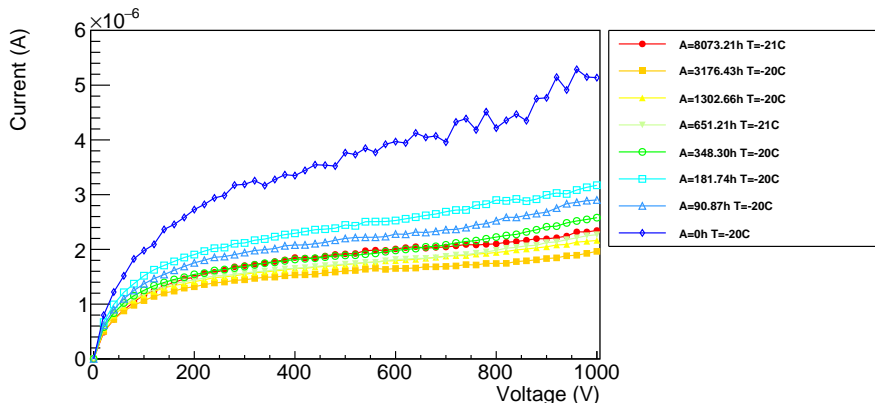


The difference between setups is small, and it might be due to differences of the thickness of the wafers, or error in the measurement (KIT have 5% error in the measurement).

Thanks to Liv and Cedric for the data!

Irradiated FZ samples with 23 MeV protons

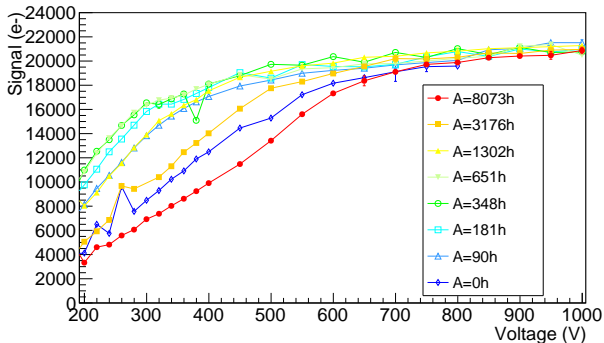
Measurements for a FZ diode
FZ: Fluence = $3 \times 10^{14} n_{eq}/cm^2$



Irradiated FZ samples with 23 MeV protons

Measurements taken with the same ALiBaVa board and ^{90}Sr radioactive source at -20°C
Trigger events 100000

Nitrostrip: FZ wafer Fluence = $3 \times 10^{14} n_{\text{eq}}/\text{cm}^2$



Once depleted, the detectors have:

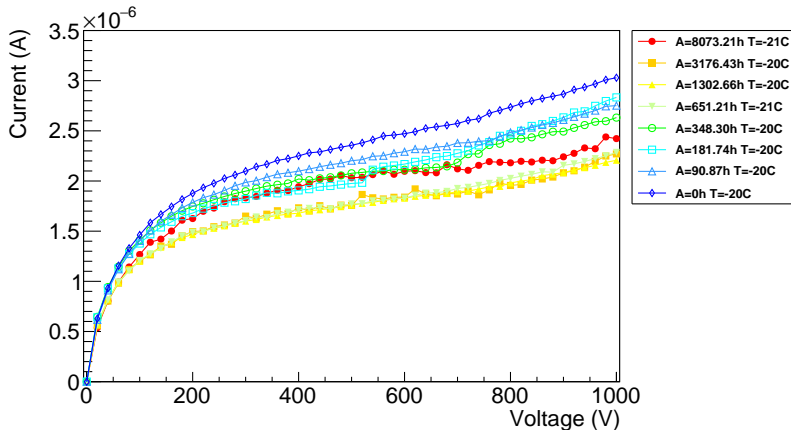
■ FZ $\sim 21\text{ke}^-$

Measurement uncertainty estimated to be $\sim 5\%$

Irradiated Nit samples with 23 MeV protons

Measurements from a Nitrogen enriched diode

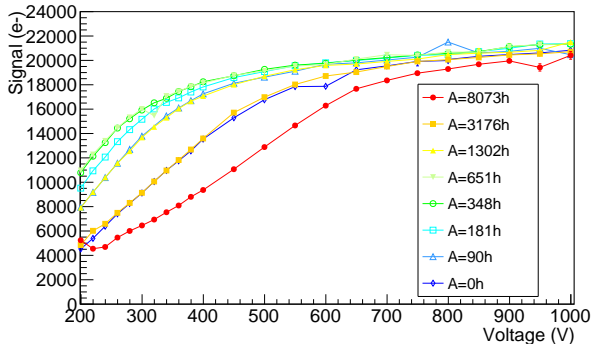
Nit: Fluence = $3 \times 10^{14} n_{eq}/cm^2$



Irradiated Nit samples with 23 MeV protons

Measurements taken with the same ALiBaVa board and ^{90}Sr radioactive source at -20°C
Trigger events 100000

Nitrostrip: Nit wafer Fluence = $3 \times 10^{14} n_{\text{eq}}/\text{cm}^2$



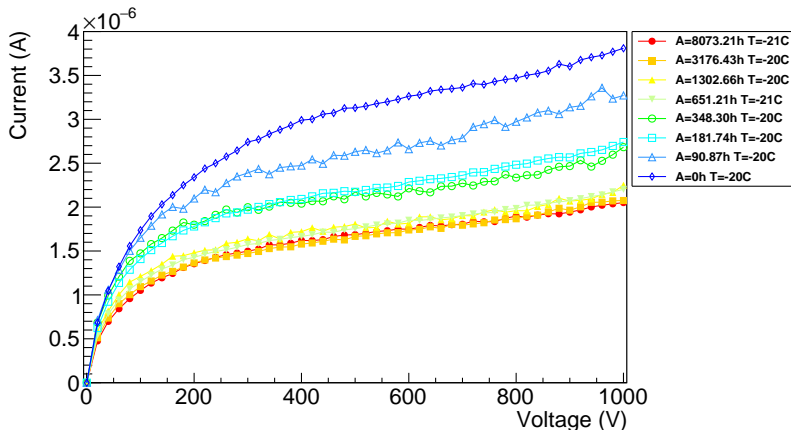
Once depleted, the detectors have:

■ Nit $\sim 21\text{ke}^-$

Measurement uncertainty estimated to be $\sim 5\%$

Irradiated DOFZ samples with 23 MeV protons

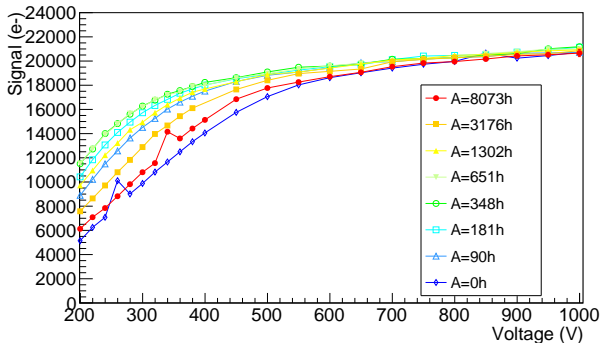
Measurements from a DOFZ diode
DOFZ: Fluence = $3 \times 10^{14} n_{eq}/cm^2$



Irradiated DOFZ samples with 23 MeV protons

Measurements taken with the same ALiBaVa board and ^{90}Sr radioactive source at -20°C
Trigger events 100000

Nitrostrip: DOFZ wafer Fluence = $3 \times 10^{14} n_{\text{eq}}/\text{cm}^2$



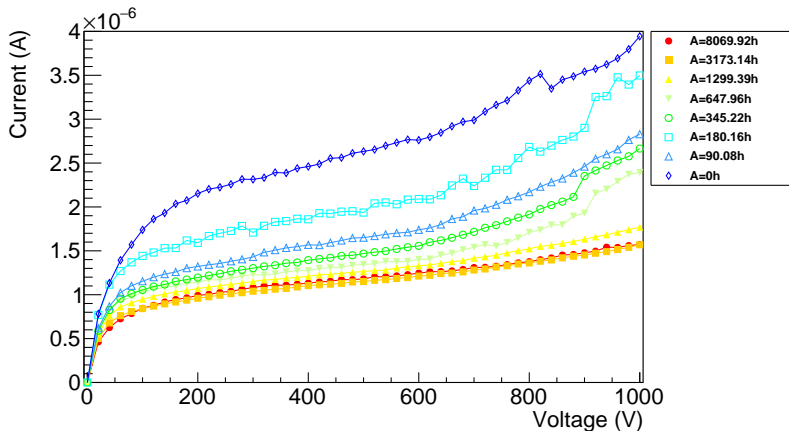
Once depleted, the detectors have:

■ DOFZ $\sim 21\text{ke}^-$

Measurement uncertainty estimated to be $\sim 5\%$

Irradiated MCz samples with 23 MeV protons

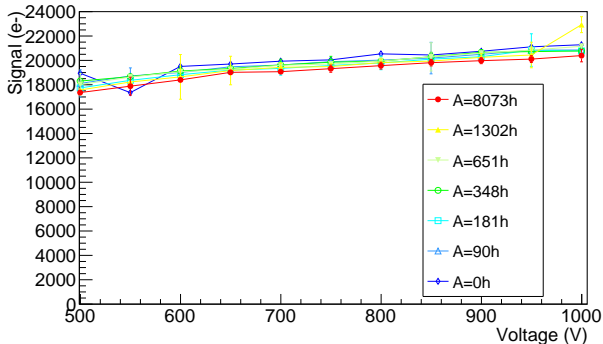
Measurements from a MCz diode
MCz: Fluence = $3 \times 10^{14} n_{eq}/cm^2$



Irradiated MCz samples with 23 MeV protons

Measurements taken with the same ALiBaVa board and ^{90}Sr radioactive source at $-20\text{ }^\circ\text{C}$
Trigger events 100000

Nitrostrip: MCz wafer Fluence = $3 \times 10^{14} \text{ n}_{\text{eq}}/\text{cm}^2$



Once depleted, the detectors have:

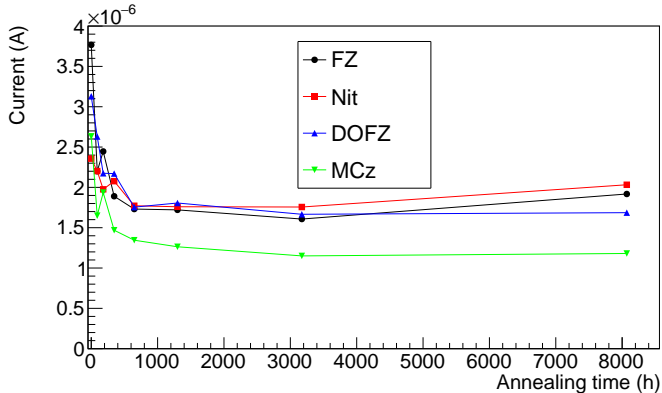
■ MCz $\sim 21\text{ke}^-$

Measurement uncertainty estimated to be $\sim 5\%$

Irradiated diodes with 23 MeV protons

Current versus annealing time

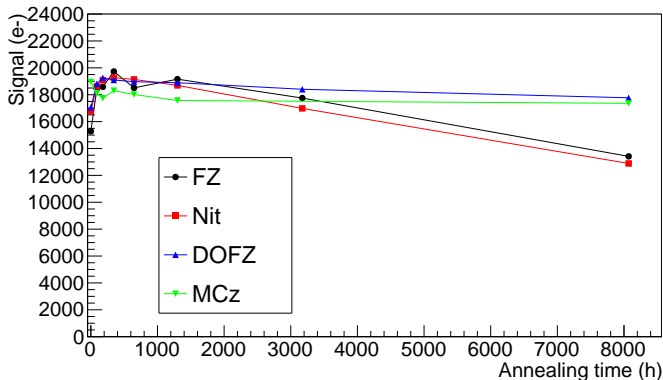
Nitrostrip: Annealing at 500V Fluence = $3 \times 10^{14} n_{eq}/cm^2$



Irradiated strips with 23 MeV protons

CCE versus annealing time

Nitrostrip: Annealing at 500V Fluence = $3 \times 10^{14} n_{eq}/cm^2$



More degradation after annealing for the FZ and Nit wafers.

- Sensors after proton irradiation show good behaviour
- Nitrogen enriched wafers do not show any improvement for the charge collection after 23 MeV proton irradiation at $3 \times 10^{14} \text{ n}_{\text{eq}}/\text{cm}^2$ regarding the other wafers

Future work

- Complete initial measurement program
- edge-TCT measurements, DLTS, ...

Acknowledgements



This project has received funding from the European Union's Horizon 2020 research and innovation programme under grant agreement No 654168



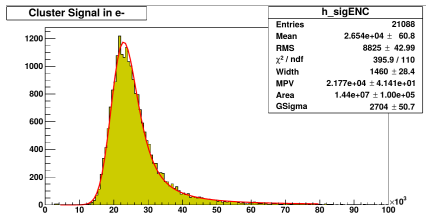
AIDA²⁰²⁰

Backup

Measurements with trigger attenuation

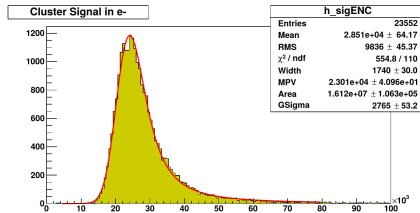
Some measurements were taken with a silicon piece between the sensor and the scintillator. Measurements taken for the MCz wafer

With silicon piece



■ MPV 21700 electrons

Without the silicon piece



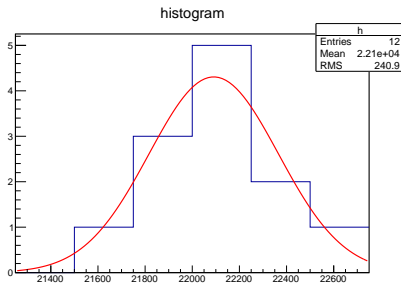
■ MPV 23010 electrons

5% difference between the two measurements

Error and attenuation

Error associated in the measurement is approximately 5%

Repetition of the same measurement several times without changing the conditions



$$\sigma = 274e^{-}$$